

**Amendments to the Specification**

Please replace the paragraph beginning on page 8, line 9 of the original specification with the following amended paragraph:

In certain embodiments of the invention, the chamber housing 401 includes a first fluid inlet 449 and a first fluid outlet 447 in communication with the processing chamber 402. Preferably, the semiconductor wafer processing apparatus 400 includes a first fluid communication line 440 coupling the first fluid outlet 447 and the first fluid inlet ~~449~~439. Preferably, the first fluid communication line 440 is integrally formed in a wall of the chamber housing 401. In one embodiment, the first fluid communication line 440 includes a first pump 446 for generating a high-velocity fluid stream. In one embodiment, a first filtering means 443 is coupled to the first fluid communication line 440. Preferably, the first filtering means 443 is configured to reduce a contaminant level of the processing fluid.